

ANNEALSYS

**Come to Annealsys Workshop Wednesday May 13 at 9h30
held during the E-MRS Spring meeting in Lille**

From RTP to CVD and from CVD to ALD

**Learn more about our solutions for RTP and RTCVD
and our multi process capability RTP machines up to 2000°C.**

- **Rapid Thermal Annealing (RTA)**
 - Implant annealing
 - Ohmic contact annealing
 - Rapid Thermal Oxidation (RTO)
 - **Selenization**
 - Diffusion of spin-on dopants
 - Densification and crystallization
 - **CVD of graphene**
 - **CVD of hexagonal boron nitride (hBN)**
 - Carbon nanotubes
 - **Poly silicon, SiO₂, SiN_x...**
 - Etc.
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**Learn more about our solutions for CVD and ALD
and our multi process capability DLI-CVD / DLI-ALD systems**

- Simple and multi-metallic oxides
- Metals, nitrides and alloys
- III-V, wide band gap semiconductors
- Nanotubes and nanowires

DLI-CVD, DLI-ALD, MOCVD, pulse pressure CVD, RTP, RTCVD inside the same process chamber !

Annealsys sponsoring

Symposium C: Advanced inorganic materials and structures for photovoltaics.

Symposium M: Multifunctional binary and complex oxides films and nanostructures for nanoelectronics and energy applications - II

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